



# **EUV Mask Pellicle TWG**

Maastricht, the Netherlands  
October 4<sup>th</sup>, 2015

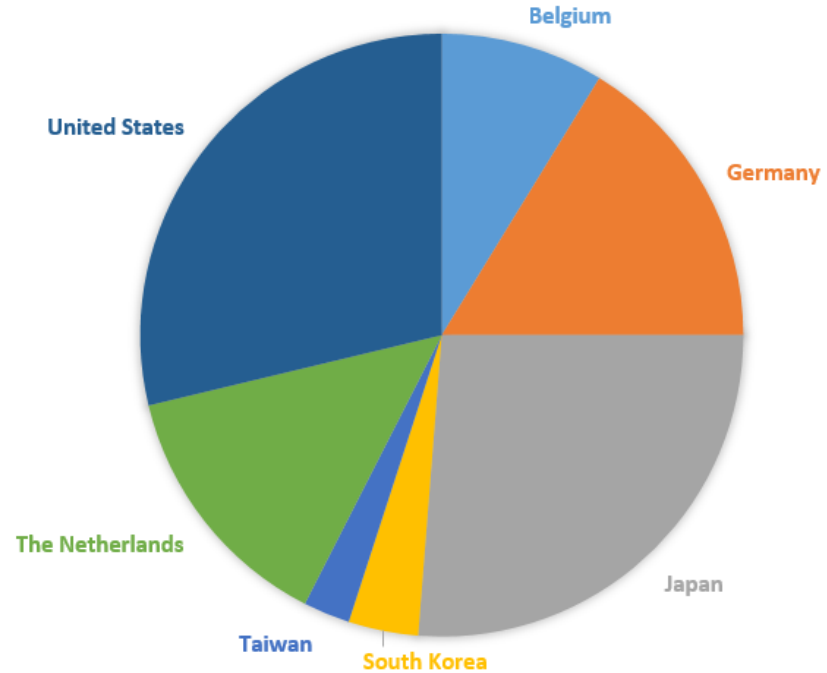


# Demographics of pellicle TWG attendees

~90 registrants

~40 companies

Good geographic  
representation



# What to expect today

15 speakers bringing different perspectives on the EUV pellicle

All material is non-confidential

Requested of each speaker: **indicate whether you think that the EUV pellicle is ready now (2015) or will be in 2020.**

**Total time per speaker is 10 minutes.** This includes questions. I will be strict about time.

Two breaks in agenda for additional discussion

# EUV Mask Pellicle TWG, Sunday October 4th, 2015

1 to ~ 4:30pm

	Affiliation	Speaker
<b>Introduction:</b> goals, structure of agenda, etc.	imec	Emily Gallagher
<b>1. Pellicle requirements from industry:</b>		
NXE pellicle progress update	ASML	Dan Smith
TSMC perspective on the EUV pellicle	TSMC	Jack Chen
Issues with the Si based EUV pellicle	Samsung	Sungwon Kwon
EUV Pellicle manufacturability	Intel	Ted Liang
Globalfoundries' perspective on the EUV pellicle	GF	Eric Hosler
<b>2. Membrane development</b>		
Pellicle Membrane Development at Luxel Corporation	Luxel	Travis Ayers
Graphene pellicles	ANL	Richard van Rijn
Pellicle membrane development at Norcada/Exogenesis	Norcada/Exogenesis	Sean Kirkpatrick
Pellicle membrane development at imec	imec	Johannes Vanpaemel
<b>discussion/buffer/break</b>		
<b>3. Membrane metrology</b>		
EUV optical characterization and lifetime testing facilities of PTB	PTB	Christian Laubis
Challenges of the in-lab pellicle transmission metrology	RTWH	Serhiy Danyluk
Recent pellicle transmission measurement results	EUVTech	Chami Perera
<b>4. Supply chain update:</b>		
FST's status & inspection system for EUV Pellicle	FST	Donwon Park
Cleaning tool supplier perspective	Suss	Jens Kruemberg
Entegris progress/status of pellicle capable EUV pods	Entegris	Chris Newman
<b>Wrap-up &amp; Discussion all</b>		